

Form 1449*

Atty. Docket No.: 303.603US1

Serial No. 09/382,929

INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

Applicant: Paul A. Farrar

Filing Date: August 25, 1999

Group: 2936

(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

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	Chiniwalla, N., et al., "Structure-Property Relations for Polynorbornenes", <u>Proceedings from the Eighth Meeting of the Dupont Symposium on Polyimides in Microelectronics</u> , pp. 615-642, (1998)
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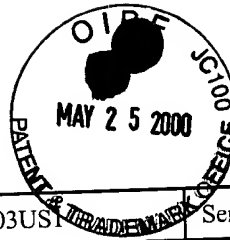
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Sheet 2 of 2

Form 1449*	Atty. Docket No.: 303.603US1	Serial No. 09/382,929
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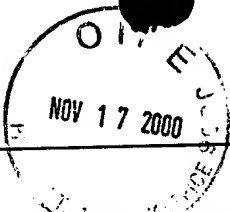
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